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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/945,316	08/30/2001	Ulrich C. Boettiger	108298547US	1351

25096 7590 07/25/2003

PERKINS COIE LLP
PATENT-SEA
P.O. BOX 1247
SEATTLE, WA 98111-1247

EXAMINER

YOUNG, CHRISTOPHER G

ART UNIT

PAPER NUMBER

1756

DATE MAILED: 07/25/2003

10

Please find below and/or attached an Office communication concerning this application or proceeding.

Interview Summary

Application No. 09/945,316	Applicant(s) Boettiger et al.
Examiner Chris Young	Art Unit 1756

All participants (applicant, applicant's representative, PTO personnel):

(1) Chris Young

(3) Aaron Poledna

(2) John Wechkin

(4) _____

Date of Interview Jul 24, 2003

Type: a) Telephonic b) Video Conference
c) Personal [copy is given to 1) applicant 2) applicant's representative]

Exhibit shown or demonstration conducted: d) Yes e) No. If yes, brief description:

Claim(s) discussed: 1-45, claims 1, 15, 22, 29 and 35 in particular

Identification of prior art discussed:

Mei et al. '867, Cooper et al. '110, Ishikawa '550, Stanton '566 and Shiraishi et al. '740

Agreement with respect to the claims f) was reached. g) was not reached. h) N/A.

Substance of Interview including description of the general nature of what was agreed to if an agreement was reached, or any other comments:

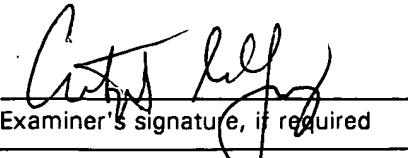
Discussed the proposed amendments and how they appear to define the claims over the applied prior art of record. This was in regards to claims 1 and 15, and their dependents. Discussed the feedback loop of claims 35-45 and how the Examiner would interpret these claims as including a reticle inherently, and as such, would appear to define over the applied reference. Applicants representatives stated they would think about Festo issue and decide whether the claims would be amended. Finally, claims 22-34 were discussed and it was agreed that the scope appears to be taught by Stanton '566. The Examiner was told that these claims would be cancelled.

(A fuller description, if necessary, and a copy of the amendments which the examiner agreed would render the claims allowable, if available, must be attached. Also, where no copy of the amendments that would render the claims allowable is available, a summary thereof must be attached.)

i) It is not necessary for applicant to provide a separate record of the substance of the interview (if box is checked).

Unless the paragraph above has been checked, THE FORMAL WRITTEN REPLY TO THE LAST OFFICE ACTION MUST INCLUDE THE SUBSTANCE OF THE INTERVIEW. (See MPEP section 713.04). If a reply to the last Office action has already been filed, APPLICANT IS GIVEN ONE MONTH FROM THIS INTERVIEW DATE TO FILE A STATEMENT OF THE SUBSTANCE OF THE INTERVIEW. See Summary of Record of Interview requirements on reverse side or on attached

CHRIS YOUNG
PRIMARY EXAMINER
ART UNIT 1756


Examiner's signature, if required

Examiner Note: You must sign this form unless it is an Attachment to a signed Office action.

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09/ 945, 316

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**PROPOSED CLAIM AMENDMENTS
FOR DISCUSSION PURPOSES ONLY**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Ulrich C. Boettiger *et al.*
Application No. : 09/945,316
Filed : August 30, 2001
For : METHOD AND APPARATUS FOR CONTROLLING
RADIATION BEAM INTENSITY DIRECTED TO
MICROLITHOGRAPHIC SUBSTRATES
Examiner : Christopher G. Young
Art Unit : 1756
Docket No. : 108298547US
Date : July 24, 2003

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**PROPOSED CLAIM AMENDMENTS FOR
DISCUSSION PURPOSES ONLY**

1. (Original) A method for controlling an intensity distribution of radiation directed to a microlithographic substrate, comprising:

 directing a radiation beam from a radiation source along a radiation path, the radiation beam having a first distribution of intensity as a function of location in a plane generally transverse to the radiation path;

 impinging the radiation beam on an adaptive structure positioned in the radiation path;

 changing an intensity distribution of the radiation beam from the first distribution to a second distribution different than the first distribution by changing a state of a first portion of the adaptive structure relative to a second portion of the adaptive structure;

directing the radiation beam away from the adaptive structure along the radiation path; and

passing the radiation beam directed away from the adaptive structure through a reticle positioned between the adaptive structure and the microlithographic substrate; and

~~impinging the radiation beam directed away from the adaptive structure on the microlithographic substrate.~~

15. (Original) A method for controlling an intensity distribution of radiation directed to a microlithographic substrate, comprising:

directing a radiation beam from a radiation source along a radiation path toward a microlithographic substrate;

impinging a first portion of the radiation beam on a first portion of a selectively transmissive medium and impinging a second portion of the radiation beam on a second portion of the selectively transmissive medium;

changing a transmissivity of at least one of the first and second portions of the selectively transmissive medium relative to the other;

passing at least part of at least one of the first and second portions of the radiation beam through the selectively transmissive medium to impinge on the microlithographic substrate, while at least inhibiting passage of at least part of the other of the first and second portions of the radiation beam through the selectively transmissive medium; and

directing the radiation beam away from the selectively transmissive medium along the radiation path and passing the radiation beam through a reticle positioned between the selectively transmissive medium and the microlithographic substrate; and

to impinge on the radiation beam on the microlithographic substrate.

REMARKS

The foregoing claims are submitted for discussion purposes only based on our July 24, 2003, telephone interview. I will contact you regarding the above amendments.

Respectfully submitted,
Perkins Coie LLP

John M. Wechkin
Registration No. 42,216

JMW:ap

PERKINS COIE LLP
P.O. Box 1247
Seattle, Washington 98111-1247
(206) 583-8888
FAX: (206) 583-8500